

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	("6767824").PN.	USPAT	OR	OFF	2006/07/22 19:01
S1	8206	((438/622) or (438/624) or (438/637) or (438/638) or (438/639) or (438/671) or (438/672) or (438/687)).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/01 07:50
S2	2636	((((438/622) or (438/624) or (438/637) or (438/638) or (438/639) or (438/671) or (438/672) or (438/687)).CCLS.) and (damascene or (trench and via)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/16 22:41
S3	41	(((((438/622) or (438/624) or (438/637) or (438/638) or (438/639) or (438/671) or (438/672) or (438/687)).CCLS.) and (damascene or (trench and via))) and (hard adj mask) and (barc or (bottom adj anti adj reflect\$3)) and (resist or photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/01 10:41
S4	243	(((((438/622) or (438/624) or (438/637) or (438/638) or (438/639) or (438/671) or (438/672) or (438/687)).CCLS.) and (damascene or (trench and via))) and ((first or second) near10 (hard adj mask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/01 10:42
S5	29	(((((438/622) or (438/624) or (438/637) or (438/638) or (438/639) or (438/671) or (438/672) or (438/687)).CCLS.) and (damascene or (trench and via))) and (hard adj mask) and (barc or (bottom adj anti adj reflect\$3)) and (resist or photoresist)) and ((first or second) near10 (hard adj mask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/16 21:46
S6	44	(((((438/622) or (438/624) or (438/637) or (438/638) or (438/639) or (438/671) or (438/672) or (438/687)).CCLS.) and (damascene or (trench and via))) and (hard adj mask) and (barc or (bottom adj anti adj reflect\$3)) and (resist or photoresist)) and ((first or second) near10 (hard adj mask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/22 17:02
S7	7	S6 and (plasma same etch\$3 same polymer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/16 22:30

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S8	2	S6 and (plasma same etch\$3 same residue same polymer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/16 22:30
S9	3507	((((438/622) or (438/624) or (438/637) or (438/638) or (438/639) or (438/671) or (438/672) or (438/687)). CCLS.) and (damascene or (trench and via)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/16 22:41
S10	1	"20030176058"	US-PGPUB; USPAT	OR	OFF	2006/05/01 07:50
S11	1	"20050110152"	US-PGPUB; USPAT	OR	OFF	2006/05/01 07:50
S12	0	S10 and S11	US-PGPUB; USPAT	OR	OFF	2006/05/01 07:50
S13	2	((("20030176058") or ("20050110152")).PN.	US-PGPUB; USPAT	OR	OFF	2006/05/01 08:21
S14	2	((("20040192058") or ("20020173160")).PN.	US-PGPUB; USPAT	OR	OFF	2006/05/01 08:21
S15	48	(((((438/622) or (438/624) or (438/637) or (438/638) or (438/639) or (438/671) or (438/672) or (438/687)).CCLS.) and (damascene or (trench and via))) and (hard adj mask) and (barc or (bottom adj anti adj reflect\$3)) and (resist or photoresist)) and ((first or second) near10 (hard adj mask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/22 19:01